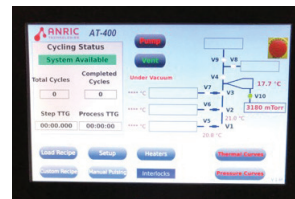


# Table - Top Atomic Layer Deposition System 4 inch

ALD technology has taken a leap in the past couple of years. SPS-Europe offers various systems, including a table top version for surface controlled layer-by-layer deposition with atomic layer accuracy.



Analog pressure controller for quick pressure check and pulse monitoring.



7" touchscreen display with complete control over operation of the tool, recipe generation and sensor data. Easy to use and robust control SW interface

**NEW! 6" systems also available! AT610**

## R&D system for growing conformal thin films at smaller scales

Large substrate and precursor temperature ranges

- Chamber temperatures from RT to 350 °C ± 1 °C
- Precursor temperatures from RT to 150 °C ± 2 °C with opt. heating jackets

Fast cycling capability

- 6-10 cycles/min or up to 1.2 nm/min of Al<sub>2</sub>O<sub>3</sub> (best in class)

Up to five ALD precursor sources at one time

- Three (3) organometallic or other metal containing sources all up to 150 °C

## Table top ALD systems

There is a need for deposition equipment optimized for growing conformal thin films at smaller scales at a reasonable cost. The AT410 4" system accomplishes these goals and fills a space in the market.

The AT-410 ALD system provides a solution to conformal, conductive thin films for 3D sample prep while also providing traditional 2D coatings that are currently grown using sputtering/evaporation. The AT410 not only pushes the boundaries, but is also an effective replacement for current sample preparation processes all within a benchtop configuration at a comparable price point.

## Glovebox integration

A standard AT410 can be attached to a glove box with a glove box adapter upgrade. The system is sealed to an open side of a pressexisting or new glove box.

The deposition chamber and sample holder are completely sealed within the inert gas environment. Air sensitive materials and substrates can be handled and deposited with utmost confidence. 100% of the glove box floor and shelving will remain accessible after installation ALD system.

